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Johanson et al.

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(54) **TARGET PROFILE FOR A PHYSICAL VAPOR DEPOSITION CHAMBER TARGET**

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(**) Term: **15 Years**

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(51) **LOC (12) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/184**

(58) **Field of Classification Search**
USPC D13/182; D15/144.1, 144.2, 199
CPC H01L 21/67742; H01L 21/0226; H01L 21/02263; H01L 21/02266; H01L 21/02269; H01L 21/02271; H01L 2224/75186; H01L 2224/761185; H01L 2224/76186; H01L 2221/68363
See application file for complete search history.

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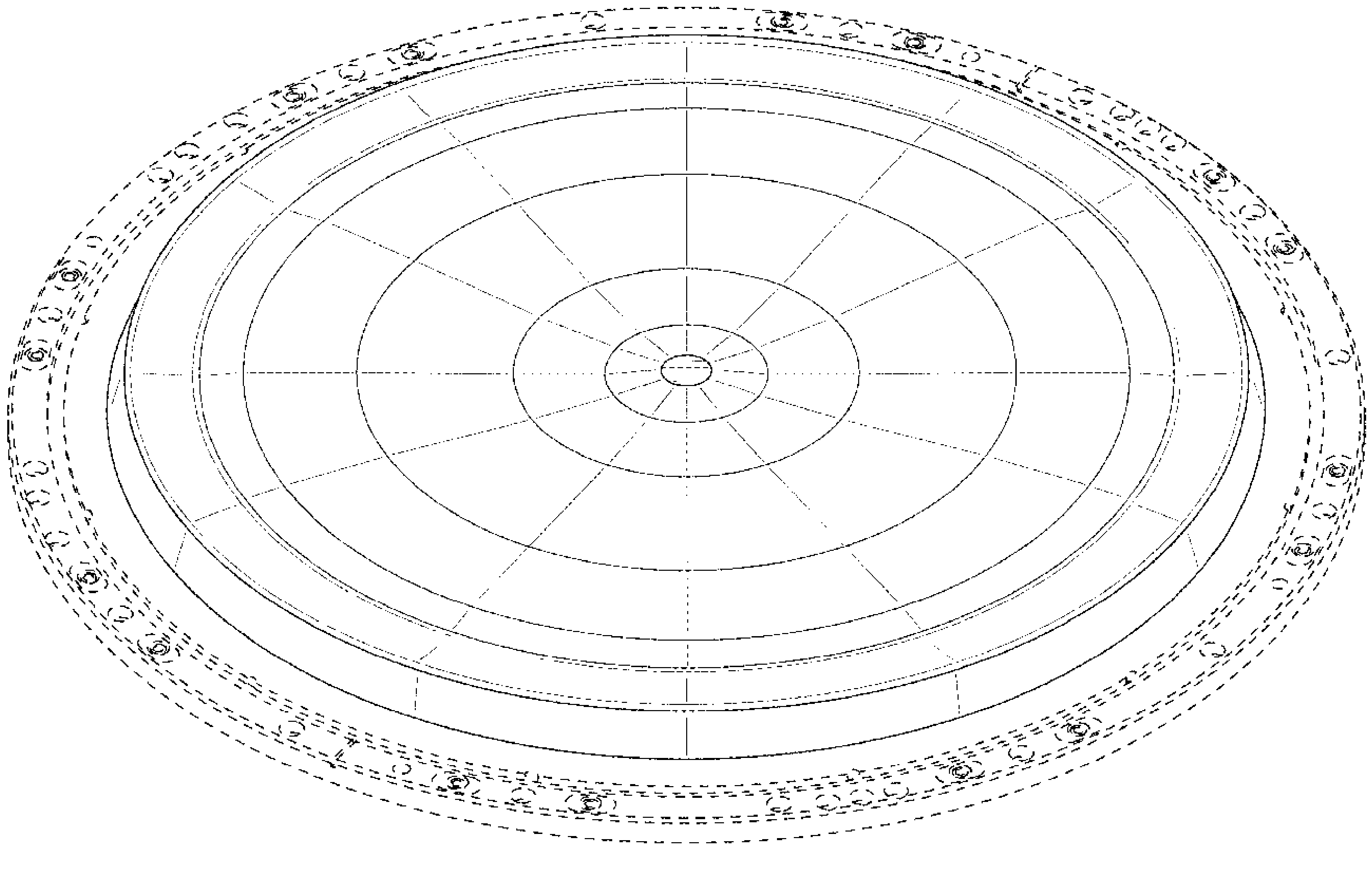
(57) **CLAIM**

We claim the ornamental design for a target profile for a physical vapor deposition chamber target, as shown and described.

DESCRIPTION

FIG. **1** is a top perspective view of a target profile for a physical vapor deposition chamber target, according to the new design.
FIG. **2** is a bottom perspective view thereof.
FIG. **3** is a top plan view thereof.
FIG. **4** is a bottom plan view thereof.
FIG. **5** is a right side elevation view thereof.
FIG. **6** is a left side elevation view thereof.
FIG. **7** is a front elevation view thereof.
FIG. **8** is a back elevation view thereof; and,
FIG. **9** is an enlarged cross sectional view taken along line **9-9** in FIG. **4**.
Dashed lines in FIGS. **1-9** represent features of the target profile for a physical vapor deposition chamber target that form no part of the claimed design.

1 Claim, 7 Drawing Sheets



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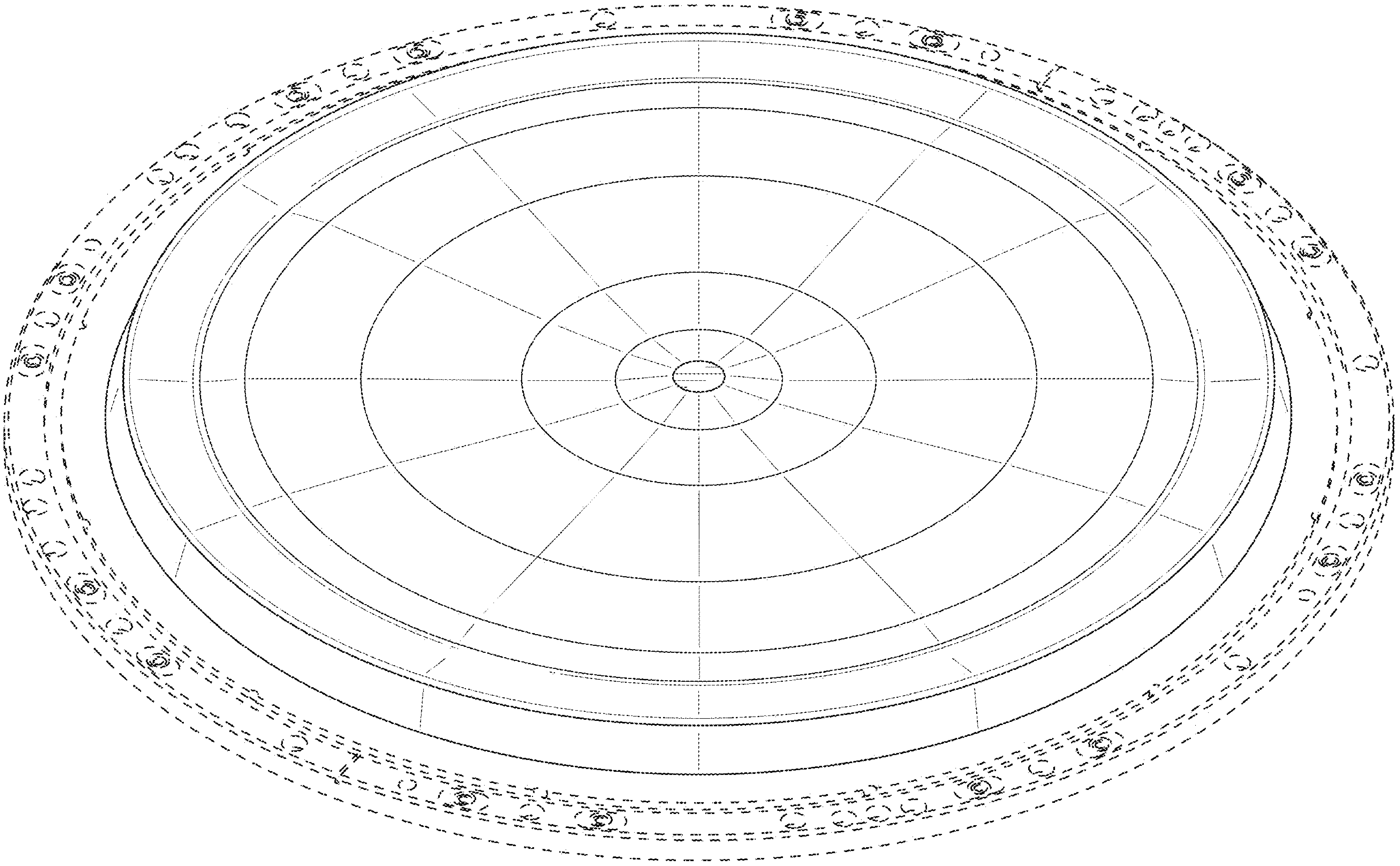

FIG. 1

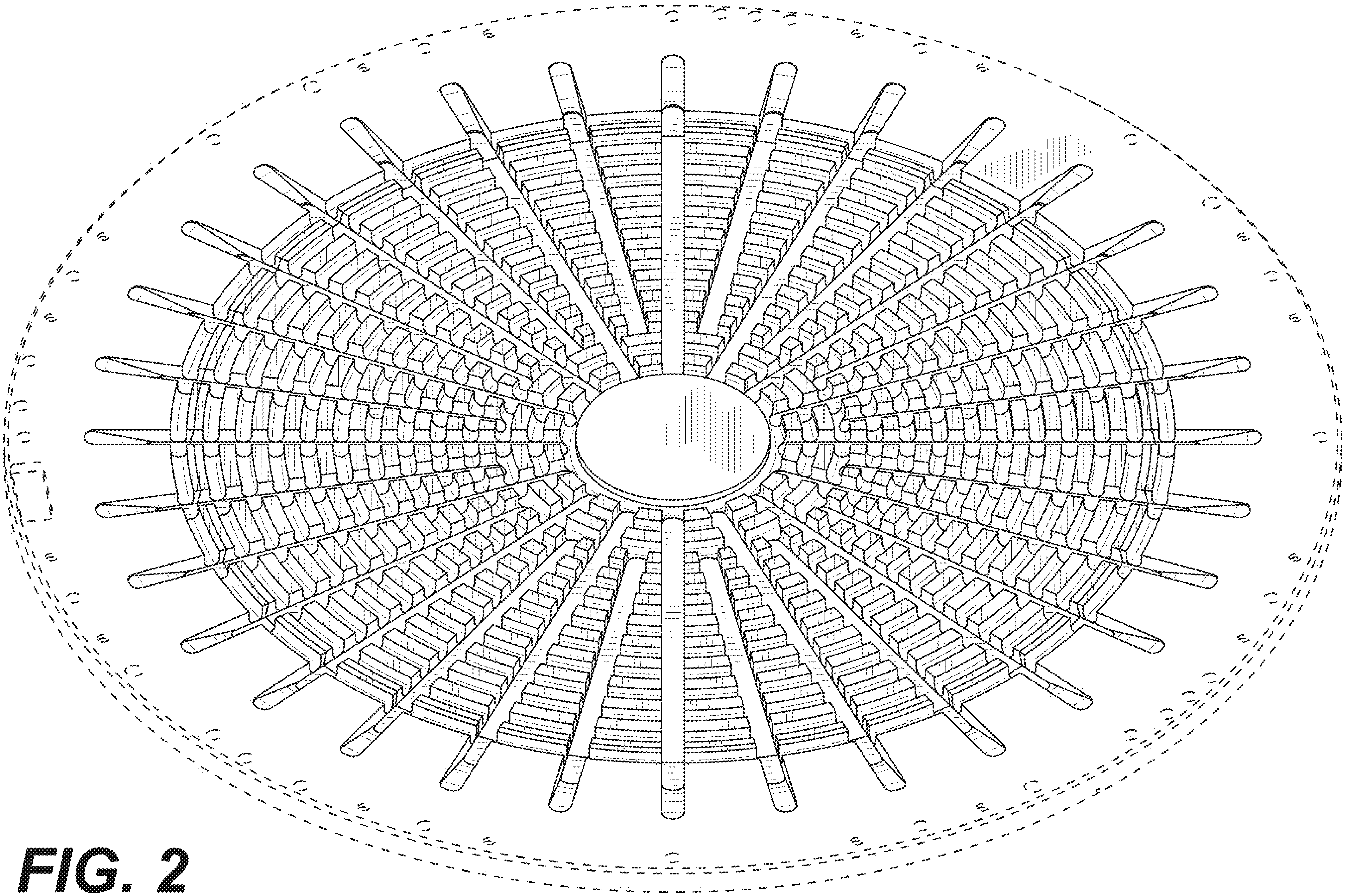

FIG. 2

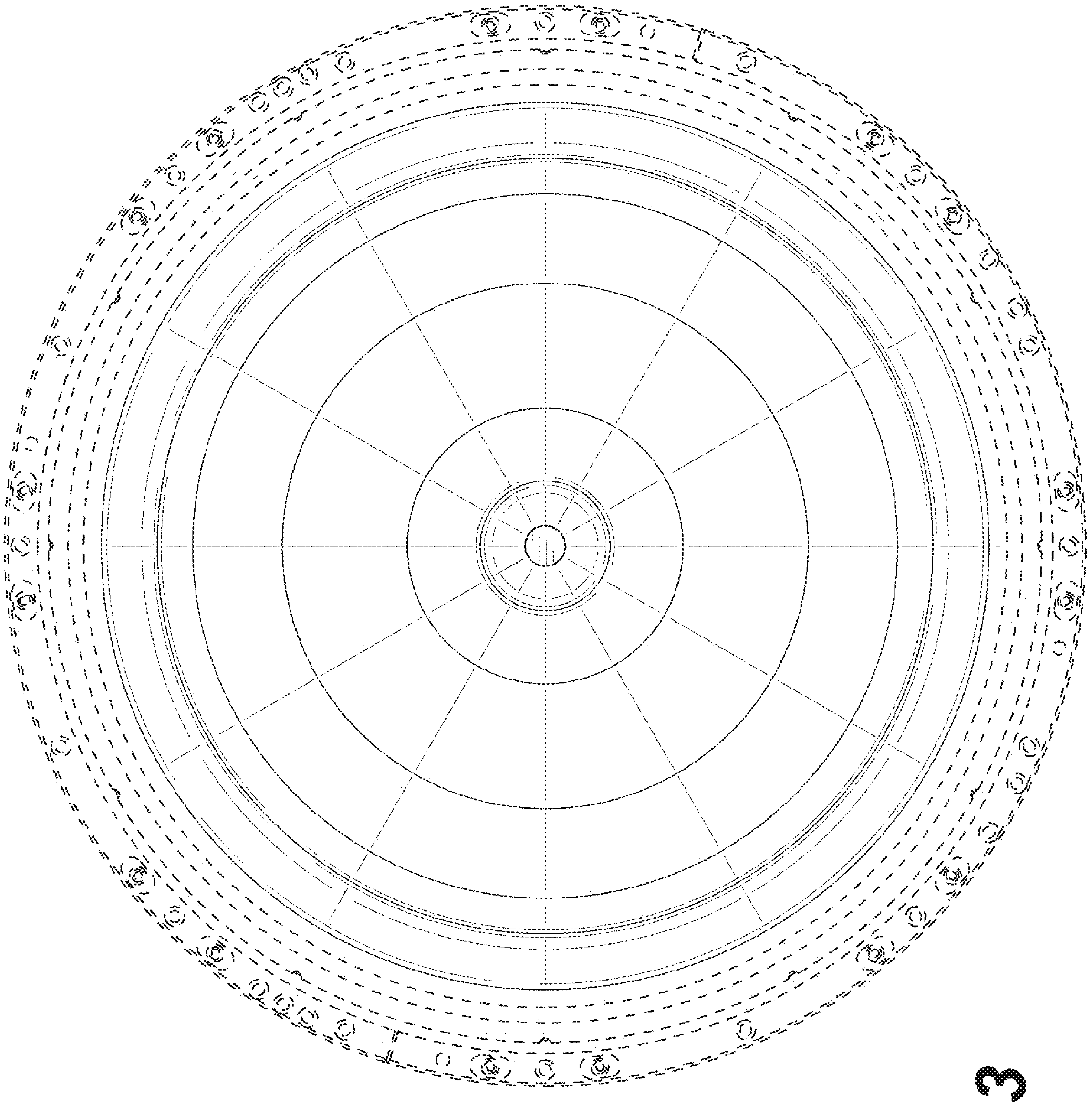

FIG. 3

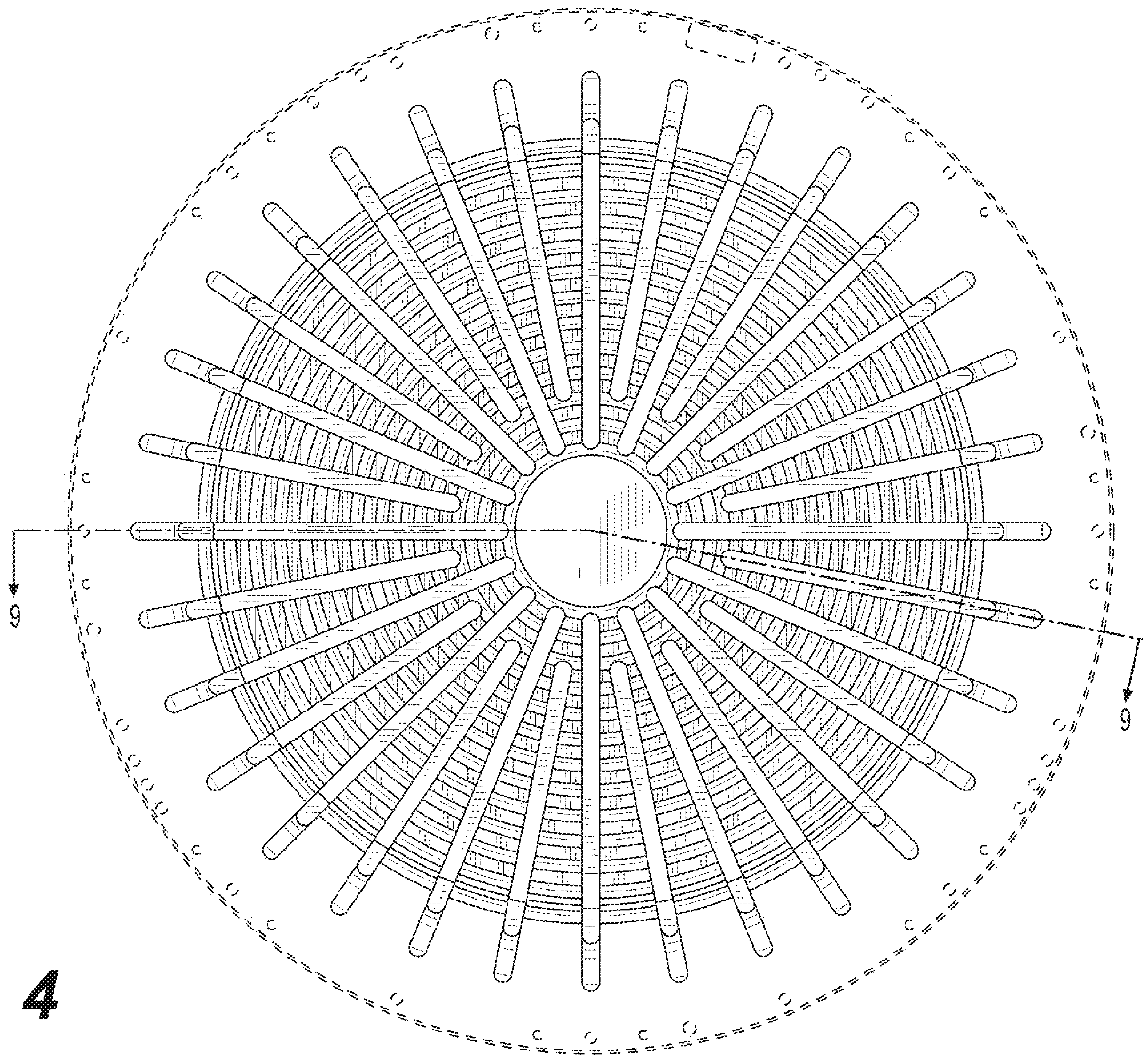

FIG. 4

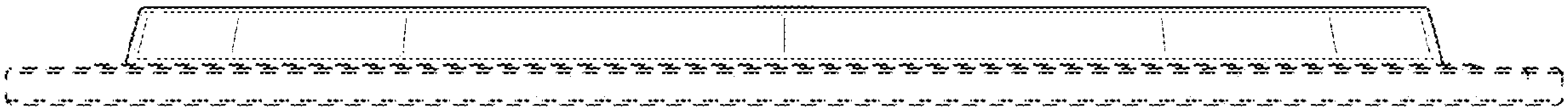

FIG. 5

FIG. 6

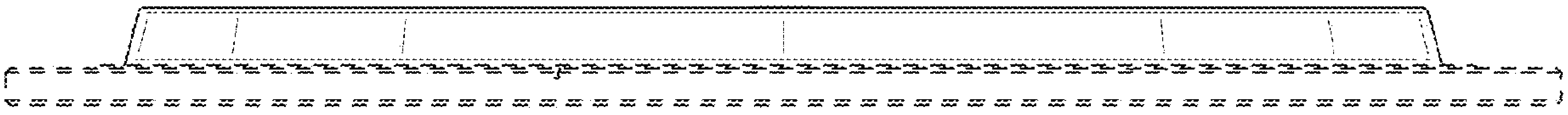

FIG. 7

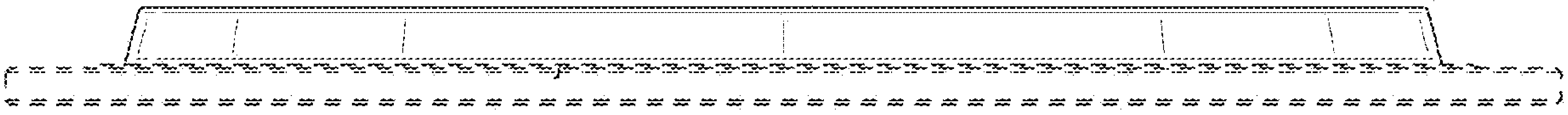

FIG. 8

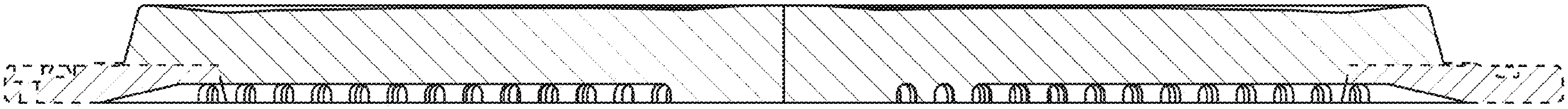

FIG. 9